

# Gregory Abadias

## List of Publications by Year in descending order

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49  
papers

2,045  
citations

279798

23  
h-index

233421

45  
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58  
all docs

58  
docs citations

58  
times ranked

2256  
citing authors

#	ARTICLE	IF	CITATIONS
1	Review Article: Stress in thin films and coatings: Current status, challenges, and prospects. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018, 36, .	2.1	482
2	Stress and preferred orientation in nitride-based PVD coatings. <i>Surface and Coatings Technology</i> , 2008, 202, 2223-2235.	4.8	228
3	Stress, interfacial effects and mechanical properties of nanoscale multilayered coatings. <i>Surface and Coatings Technology</i> , 2007, 202, 844-853.	4.8	96
4	Nanoindentation hardness and structure of ion beam sputtered TiN, W and TiN/W multilayer hard coatings. <i>Surface and Coatings Technology</i> , 2006, 200, 6538-6543.	4.8	86
5	Stress, phase stability and oxidation resistance of ternary Ti-Me-N (Me=Zr, Ta) hard coatings. <i>Thin Solid Films</i> , 2013, 538, 56-70.	1.8	73
6	Structure, phase stability and elastic properties in the Ti <sub>1-x</sub> Zr <sub>x</sub> N thin-film system: Experimental and computational studies. <i>Acta Materialia</i> , 2012, 60, 5601-5614.	7.9	71
7	On the origin of the metastable $\delta$ -Ta phase stabilization in tantalum sputtered thin films. <i>Acta Materialia</i> , 2017, 126, 481-493.	7.9	70
8	Structural and mechanical properties of NbN and Nb-Si-N films: Experiment and molecular dynamics simulations. <i>Ceramics International</i> , 2016, 42, 11743-11756.	4.8	63
9	Benefits of energetic ion bombardment for tailoring stress and microstructural evolution during growth of Cu thin films. <i>Acta Materialia</i> , 2017, 141, 120-130.	7.9	53
10	Stress evolution in magnetron sputtered Ti-Zr-N and Ti-Ta-N films studied by in situ wafer curvature: Role of energetic particles. <i>Thin Solid Films</i> , 2009, 518, 1532-1537.	1.8	51
11	Stress and microstructure evolution during growth of magnetron-sputtered low-mobility metal films: Influence of the nucleation conditions. <i>Thin Solid Films</i> , 2010, 519, 1655-1661.	1.8	50
12	Electronic structure and mechanical properties of ternary ZrTaN alloys studied by <i>ab initio</i> calculations and thin-film growth experiments. <i>Physical Review B</i> , 2014, 90, .	3.2	45
13	Real-time stress evolution during early growth stages of sputter-deposited metal films: Influence of adatom mobility. <i>Vacuum</i> , 2014, 100, 36-40.	3.5	45
14	Nanocolumnar TiN thin film growth by oblique angle sputter-deposition: Experiments vs. simulations. <i>Materials and Design</i> , 2018, 160, 338-349.	7.0	44
15	Alloying effects on the structure and elastic properties of hard coatings based on ternary transition metal (M = Ti, Zr or Ta) nitrides. <i>Surface and Coatings Technology</i> , 2014, 257, 129-137.	4.8	43
16	Three-dimensional kinetic Monte Carlo simulations of cubic transition metal nitride thin film growth. <i>Physical Review B</i> , 2016, 93, .	3.2	43
17	Epitaxial growth of Cu(001) thin films onto Si(001) using a single-step HiPIMS process. <i>Scientific Reports</i> , 2017, 7, 1655.	3.3	38
18	3D-to-2D Morphology Manipulation of Sputter-Deposited Nanoscale Silver Films on Weakly Interacting Substrates via Selective Nitrogen Deployment for Multifunctional Metal Contacts. <i>ACS Applied Nano Materials</i> , 2020, 3, 4728-4738.	5.0	38

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19	Tuning high power impulse magnetron sputtering discharge and substrate bias conditions to reduce the intrinsic stress of TiN thin films. <i>Thin Solid Films</i> , 2019, 688, 137335.	1.8	37
20	Nanoscaled composite TiN/Cu multilayer thin films deposited by dual ion beam sputtering: growth and structural characterisation. <i>Thin Solid Films</i> , 2003, 433, 166-173.	1.8	35
21	Influence of Phase Transformation on Stress Evolution during Growth of Metal Thin Films on Silicon. <i>Physical Review Letters</i> , 2010, 104, 096101.	7.8	30
22	Study of columnar growth, texture development and wettability of reactively sputter-deposited TiN, ZrN and HfN thin films at glancing angle incidence. <i>Surface and Coatings Technology</i> , 2020, 399, 126130.	4.8	30
23	Large influence of vacancies on the elastic constants of cubic epitaxial tantalum nitride layers grown by reactive magnetron sputtering. <i>Acta Materialia</i> , 2020, 184, 254-266.	7.9	26
24	Manipulation of thin silver film growth on weakly interacting silicon dioxide substrates using oxygen as a surfactant. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2020, 38, .	2.1	24
25	Influence of Al content on the phase formation, growth stress and mechanical properties of TiZrAlN coatings. <i>Thin Solid Films</i> , 2013, 538, 32-41.	1.8	22
26	Magnetron Sputtering Deposition of Ag/TiO <sub>2</sub> Nanocomposite Thin Films for Repeatable and Multicolor Photochromic Applications on Flexible Substrates. <i>Advanced Materials Interfaces</i> , 2015, 2, 1500134.	3.7	22
27	Direct Observation of the Thickness-Induced Crystallization and Stress Build-Up during Sputter-Deposition of Nanoscale Silicide Films. <i>ACS Applied Materials &amp; Interfaces</i> , 2016, 8, 34888-34895.	8.0	21
28	P-type Al-doped Cr-deficient CrN thin films for thermoelectrics. <i>Applied Physics Express</i> , 2018, 11, 051003.	2.4	21
29	Texture and Stress Evolution in HfN Films Sputter-Deposited at Oblique Angles. <i>Coatings</i> , 2019, 9, 712.	2.6	20
30	In Situ and Real-Time Nanoscale Monitoring of Ultra-Thin Metal Film Growth Using Optical and Electrical Diagnostic Tools. <i>Nanomaterials</i> , 2020, 10, 2225.	4.1	17
31	Structural and photoelectrochemical properties of Ti <sub>1-x</sub> W <sub>x</sub> O <sub>2</sub> thin films deposited by magnetron sputtering. <i>Surface and Coatings Technology</i> , 2011, 205, S265-S270.	4.8	15
32	Spectral and Color Changes of Ag/TiO <sub>2</sub> Photochromic Films Deposited on Diffusing Paper and Transparent Flexible Plastic Substrates. <i>Applied Spectroscopy</i> , 2017, 71, 1271-1279.	2.2	14
33	Structure, stress, and mechanical properties of Mo-Al-N thin films deposited by dc reactive magnetron cosputtering: Role of point defects. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2020, 38, .	2.1	12
34	A relation between the Au-surfactant effect and the chemical mixing during the epitaxial growth of Ni on Au(0 0 1). <i>Applied Surface Science</i> , 2001, 177, 273-281.	6.1	11
35	Epitaxial growth and mechanical properties of (001) ZrN/W nanolaminates. <i>Surface and Coatings Technology</i> , 2008, 202, 3683-3687.	4.8	11
36	Impact of Ge alloying on the early growth stages, microstructure and stress evolution of sputter-deposited Cu-Ge thin films. <i>Acta Materialia</i> , 2018, 159, 286-295.	7.9	10

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37	On the Nanostructure of Cu in $Ti_xCu_{1-x}$ and TiN/Cu Films: A XAFS Study. Journal of Nano Research, 2009, 6, 43-50.	0.8	8
38	Interfacial Silicide Formation and Stress Evolution during Sputter Deposition of Ultrathin Pd Layers on a-Si. ACS Applied Materials & Interfaces, 2019, 11, 39315-39323.	8.0	6
39	Manipulation of thin metal film morphology on weakly interacting substrates via selective deployment of alloying species. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2022, 40, .	2.1	6
40	Structural evolution of Au[001]/Ni MBE thin films and Au $_{1-x}$ Ni $_x$ solid solutions with temperature: a HREM study. Thin Solid Films, 1998, 318, 209-214.	1.8	5
41	Effect of temperature on the growth of TiN thin films by oblique angle sputter-deposition: A three-dimensional atomistic computational study. Computational Materials Science, 2021, 197, 110662.	3.0	5
42	Thermal Stability of TiZrAlN and TiZrSiN Films Formed by Reactive Magnetron Sputtering. Inorganic Materials: Applied Research, 2018, 9, 418-426.	0.5	4
43	$p$ -type behavior of CrN thin films via control of point defects. Physical Review B, 2022, 105, .	3.2	4
44	Structural Properties and Oxidation Resistance of ZrN/SiN $_x$ , CrN/SiN $_x$ and AlN/SiN $_x$ Multilayered Films Deposited by Magnetron Sputtering Technique. Coatings, 2020, 10, 149.	2.6	3
45	Structure, electrical, and optical properties of reactively sputter-deposited TaAlN thin films. Journal of Applied Physics, 2022, 131, 105303.	2.5	3
46	Microstructure Characterization of Multilayer Thin Coatings ZrN/Si $_3$ N $_4$ by X-Ray Diffraction Using Noncoplanar Measurement Geometry. Physica Status Solidi (A) Applications and Materials Science, 2018, 215, 1700670.	1.8	2
47	On the Stability of Multilayer ZrN/SiN $_x$ and CrN/SiN $_x$ Coatings Formed by Magnetron Sputtering to High-Temperature Oxidation. Journal of Surface Investigation, 2020, 14, 351-358.	0.5	1
48	Design of defected TaN supercells dataset for structural and elastic properties from ab initio simulations and comparison to experimental data. Data in Brief, 2020, 30, 105411.	1.0	1
49	ICMCTF 2011 Preface. Surface and Coatings Technology, 2011, 206, 1511.	4.8	0